

REMARKS


Claims 1-25 and 34-75 are pending in the application with claims 43 and 44 amended and new claims 48-75 added herein. No new matter is being presented in this application.

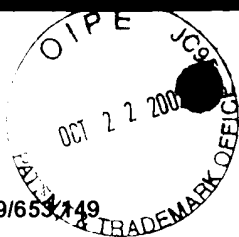
This Request for Continued Examination (RCE) Application is also being filed in an abundance of caution to permit consideration of a Supplemental Information Disclosure Statement.

Further, Applicant herewith submits copies of the Information Disclosure Statement and Form PTO-1449 filed on October 8, 2001 and July 1, 2002. No initialed copies of the Form PTO-1449 have been received back from the Examiner. To the extent that the submitted references listed on the copies of Form PTO-1449 have not already been considered, and the copies have not been initialed, such examination and initialing is requested at this time, as well as return of a copy of each initialed Form PTO-1449 to the undersigned.

Respectfully submitted,

Dated: 22 Oct 2002

By: 
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Appl. No. 09/653,149

Application Serial No. 09/653,149
Filing Date August 31, 2000
Inventor Garo J. Derderian, et al
Assignee Micron Technology, Inc.
Group Art Unit 2818
Examiner T. Le
Attorney's Docket No. MI22-1330
Title: Capacitor Fabrication Methods and Capacitor Constructions

VERSION WITH MARKINGS TO SHOW CHANGES MADE ACCOMPANYING
PRELIMINARY AMENDMENT ACCOMPANYING A RCE FILING

In the Claims

The claims have been amended as follows. Underlines indicate insertions and
strikeouts indicate deletions.

43. (amended) The method of claim 40 wherein the ~~atomic layer deposited~~
conductive material layer is formed on the first electrode, further comprising
chemisorbing additional alternating first and second precursor layers before forming the
dielectric layer.

44. (amended) The method of claim 40 wherein the ~~atomic layer deposited~~
conductive material layer comprises elemental metal, a metal alloy, or a metal
containing compound.

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